

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Satoshi TAKEI et al.

Application No.: 10/565,968

Filed: January 31, 2006

Docket No.: 126821

For: UNDERLAYER COATING FORMING COMPOSITION FOR LITHOGRAPHY
CONTAINING COMPOUND HAVING PROTECTED CARBOXYL GROUP

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:


Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- ☒ 1. This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of a first Office Action on the merits in the present application. No certification or fee is required.
- ☒ 2. Relevance of one or more non-English language reference is discussed in the specification. See References 1-8.
- ☒ 3. One or more reference cited herein was cited in the International Search Report. An English language version of the International Search Report is attached for the Examiner's information. See References 9-13.
- ☒ 4. In accordance with 37 CFR §1.98(a)(2)(ii), copies of any U.S. patents and patent application publications are not attached.
- ☒ 5. An English language Abstract of one or more non-English language reference is attached hereto. See References 1-13.

☒ 6. A computer-generated English language translation of one or more Japanese Patent Publication cited herein has been obtained from the website of the Japanese Patent Office ([<http://www.jpo.go.jp>]), and is attached, but has not been reviewed for accuracy. See References 1-3, and 5-13.

☒ 7. References 20-23 correspond to references 9 and 11-13, respectively.

Respectfully submitted,



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Date: May 15, 2006

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Form PTO-1449 (REV. 1/06)		US Dept. of Commerce PATENT & TRADEMARK OFFICE		ATTY DOCKET NO. 126821		APPLICATION NO. 10/565,968	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				APPLICANT(S) Satoshi TAKEI et al.			
				FILING DATE January 31, 2006		GROUP	
FOREIGN PATENT DOCUMENTS							
Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract	With English Translation	
	1.	JP-A-2000-294504	10-2000	Japan	X	X	
	2.	JP-A-2002-47430	02-2002	Japan	X	X	
	3.	JP-A-2002-190519	07-2002	Japan	X	X	
	4.	WO 02/05035	01-2002	WIPO	X		
	5.	JP-A-2002-128847	05-2002	Japan	X	X	
	6.	JP-A-2001-192411	07-2001	Japan	X	X	
	7.	JP-A-2000-264921	09-2000	Japan	X	X	
	8.	JP-A-07-316268	12-1995	Japan	X	X	
	9.	JP-A-2002-105137	04-2002	Japan	X	X	
	10.	JP-A-10-221855	08-1998	Japan	X	X	
	11.	JP-A-2002-97231	04-2002	Japan	X	X	
	12.	JP-A-2002-80537	03-2002	Japan	X	X	
	13.	JP-A-2002-72488	03-2002	Japan	X	X	
OTHER DOCUMENTS							
Examiner Initials	Cite No.	(Including Author, Title, Date, Pertinent Pages, etc.)					
	14.	Lynch, Tom et al., "Properties and Performance of Near UV Reflectivity Control Layers", US, in Advances in Resist Technology and Proceedings XI, Omkaram Nalamasu et., Proceedings of SPIE, 1994, Vol. 2195, pp. 225-229					
	15.	Taylor, G. et al., "Methacrylate Resists and Antireflective Coatings for 193 nm Lithography", US, in Microlithography 1999: in Advances in Resist Technology and Processing XVI, Will Conley ed., Proceedings of SPIE, 1999, Vol. 3678, pp. 174-185					
	16.	Meador, Jim D. et al., "Recent Progress in 193 nm Antireflective Coatings", US in Microlithography 1999: in Advances in Resist Technology and Processing XVI, Will Conley ed., Proceedings of SPIE, 1999, Vol 3678, pp. 800-809					
EXAMINER					DATE CONSIDERED		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

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U.S. PATENT DOCUMENTS				
Examiner Initials	Cite No.	Document Number	Date	Name
	17.	5,919,599	07-1999	Meador et al.
	18.	5,693,691	12-1997	Flaim et al.
	19.	6,686,124 B1	02-2004	Angelopoulos et al.
	20.	2002/0093069 A1	07-2002	Hong et al.
	21.	2002/0127789 A1	09-2002	Hong et al.
	22.	2002/0090452 A1	07-2002	Hong et al.
	23.	2002/0123586 A1	09-2002	Hong et al.

FOREIGN PATENT DOCUMENTS						
Examiner Initials	Cite No.	Document Number	Date	Country	With English Abstract	With English Translation

OTHER DOCUMENTS		
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